

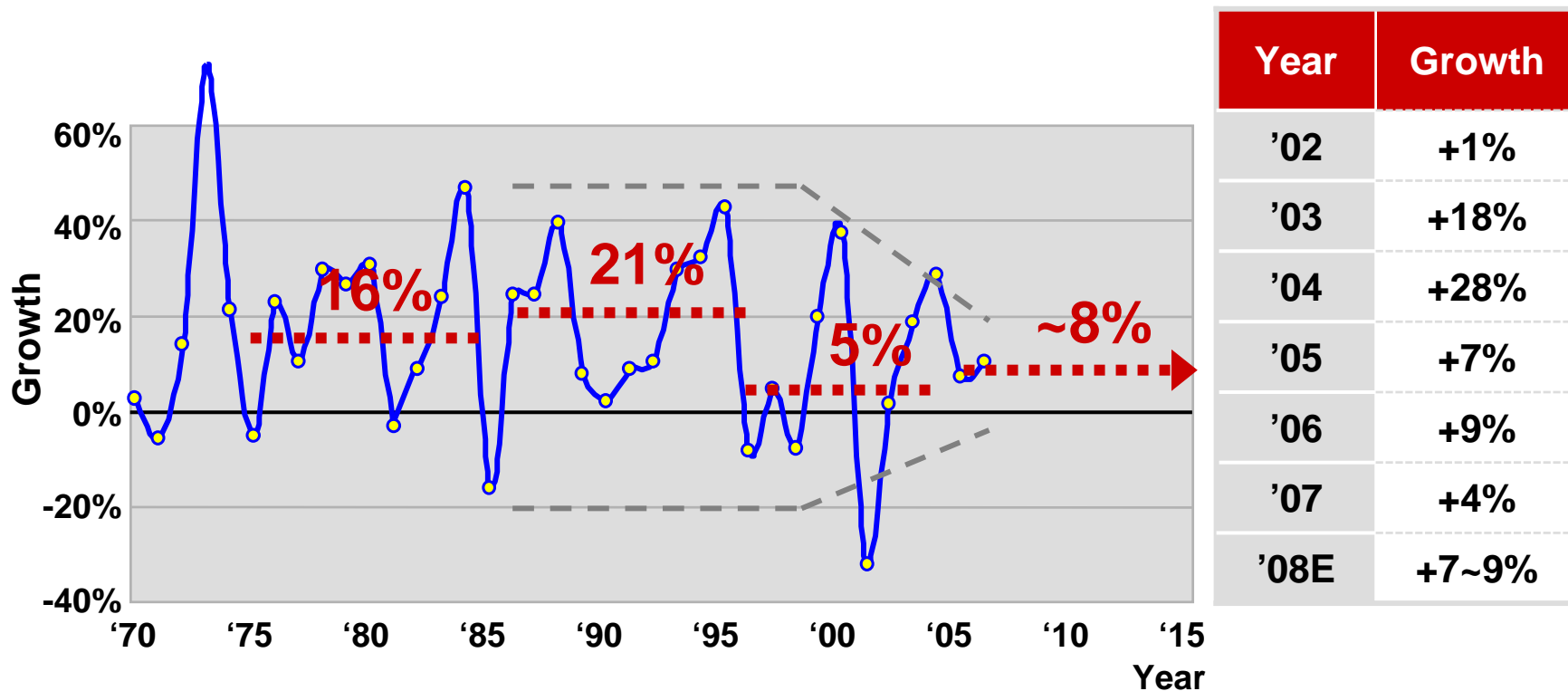
The Future of Semiconductor Industry – A Foundry's Perspective –

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Vice Chairman
TSMC
January 24, 2008**

Outline

- **Semiconductor Market Outlook**
- **Challenges and Solutions**
 - Economic
 - Technology
- **Summary**

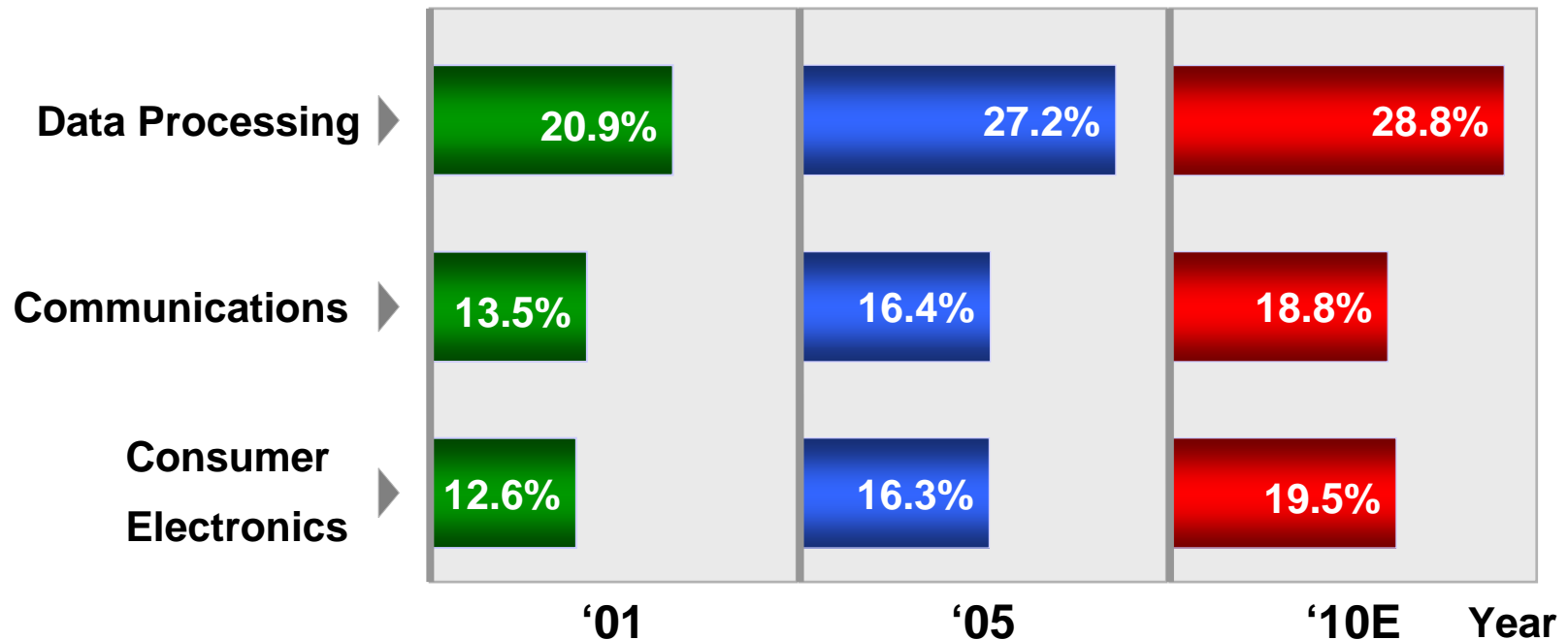
Semiconductor Market Will Continue to Grow



Source: SIA

Steady Market Expansion

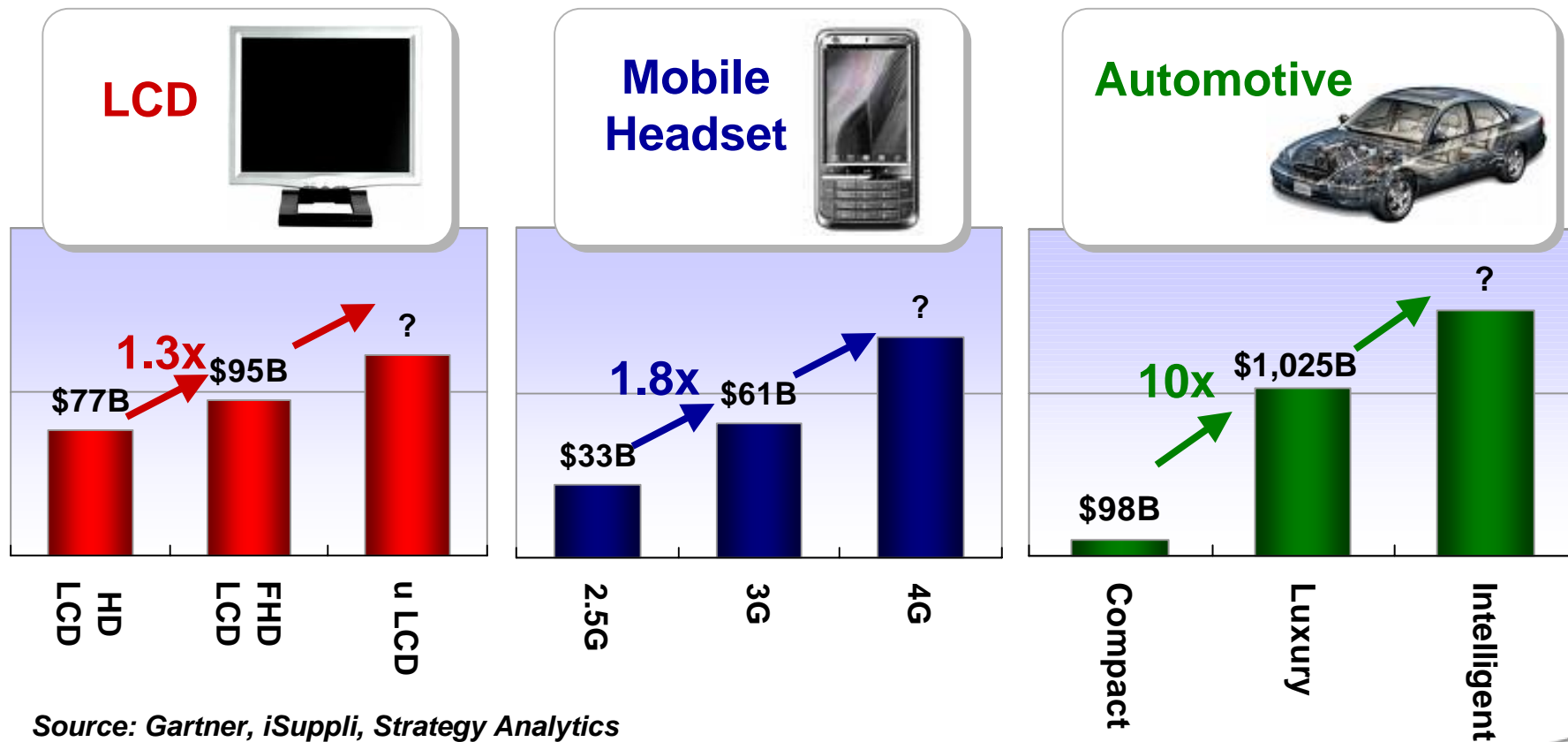
Increasing semiconductor penetration in electronics



Source: WSTS, IC Insights, TSMC estimates

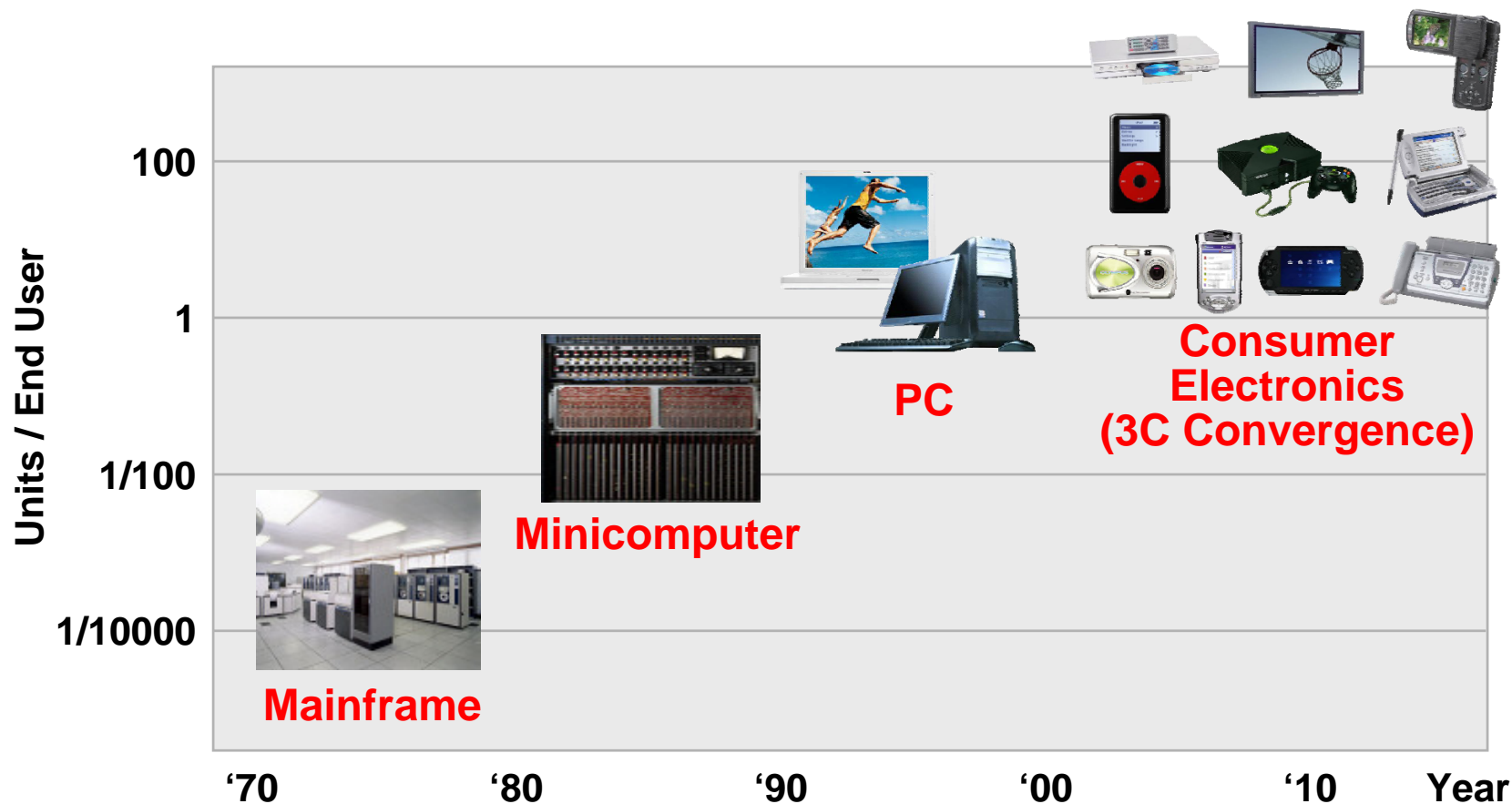
Increasing Semiconductor Content in Systems

– Functionalities and performance



Source: Gartner, iSuppli, Strategy Analytics

New Applications as Growth Drivers





In Search of A PC to Serve “The Next Billion”

- The low-cost PCs for the developing nations:



INTEL
“ClassMate”

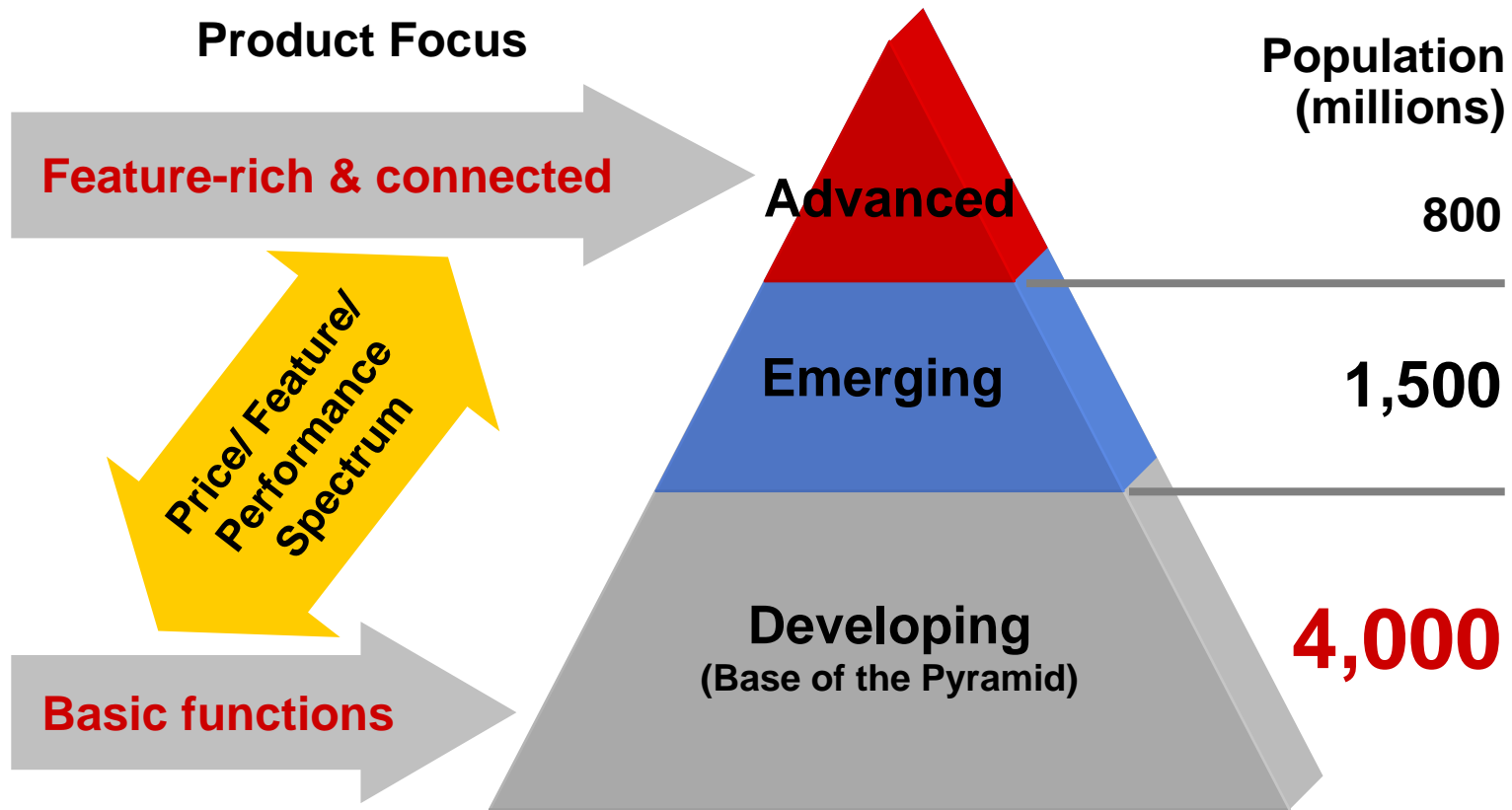


ASUS
“Eee”



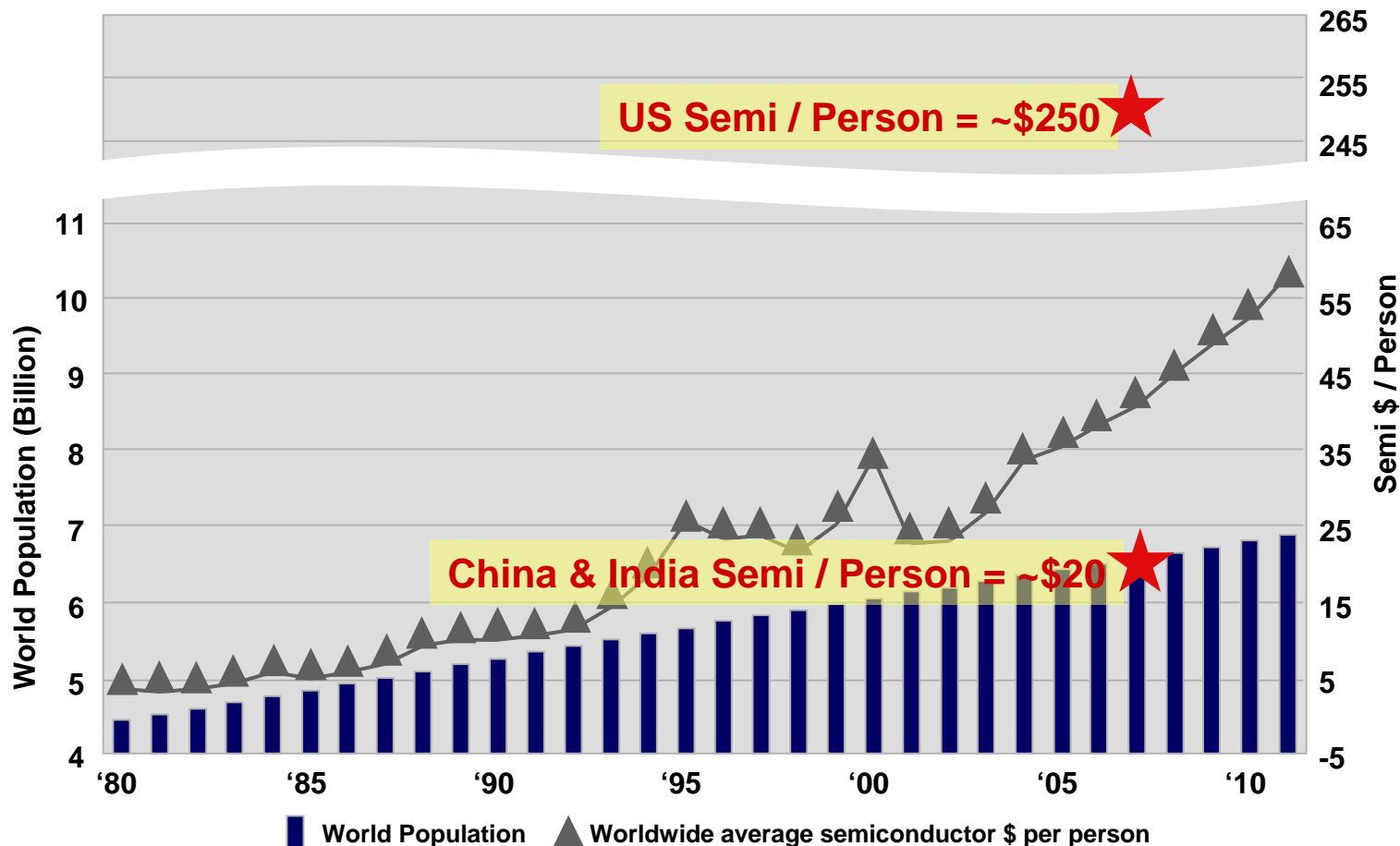
One Laptop Per Child
“XO”

Growth Opportunities are Global



Source: "The fortune at the bottom of the pyramid" by C. K. Prahalad, and IMF

Plenty of Opportunity Ahead



Source: US Census Bureau; IC-Insights; TSMC estimates

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Challenges

Economic

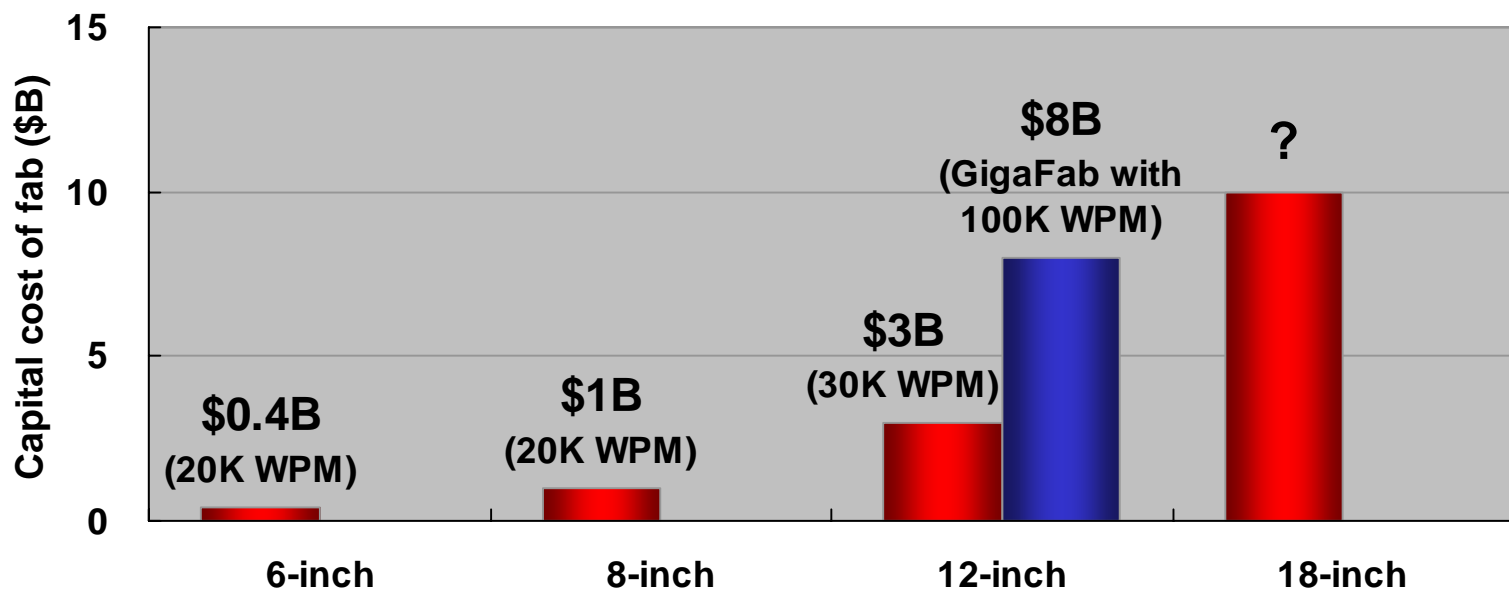
1. Huge CapEx
2. ROI Risk – Process
3. ROI Risk – Product

Technology

4. Nanometer Manufacturing
5. Nanometer Design
6. Design Complexity

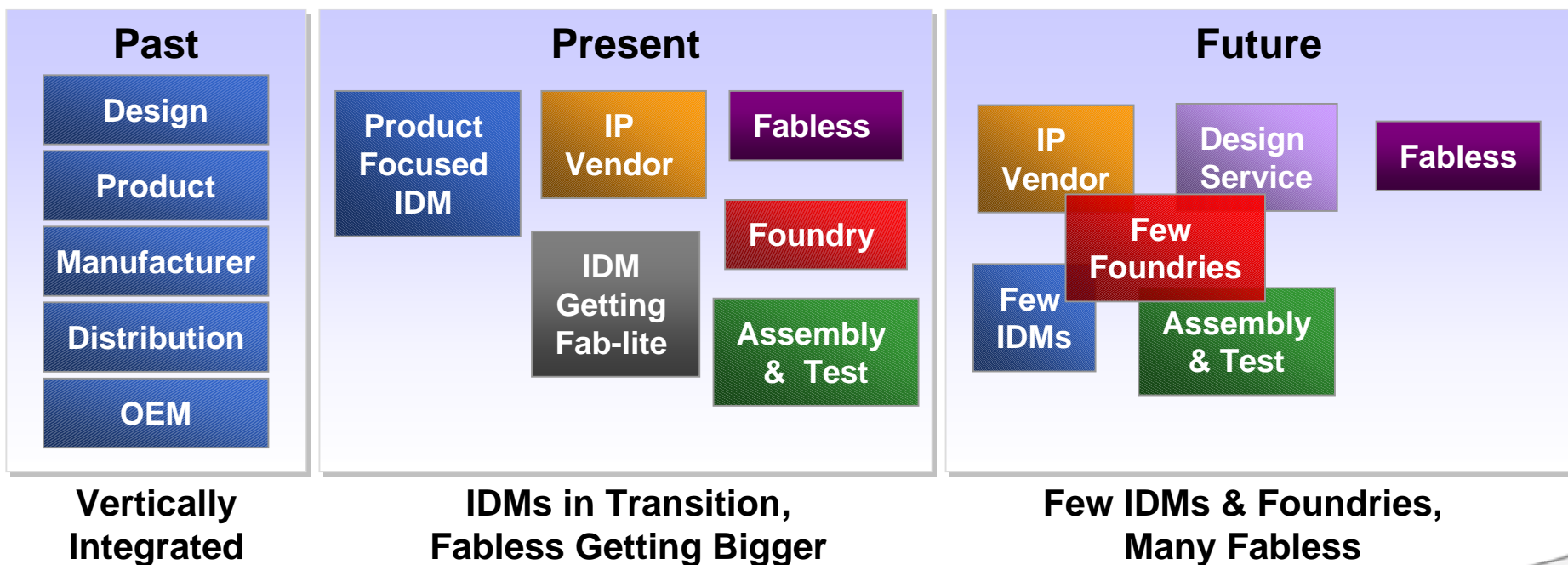
1. Huge CapEx

- Capital expenditure for constructing a new fab is rapidly increasing
 - Major factor for financing and future profit



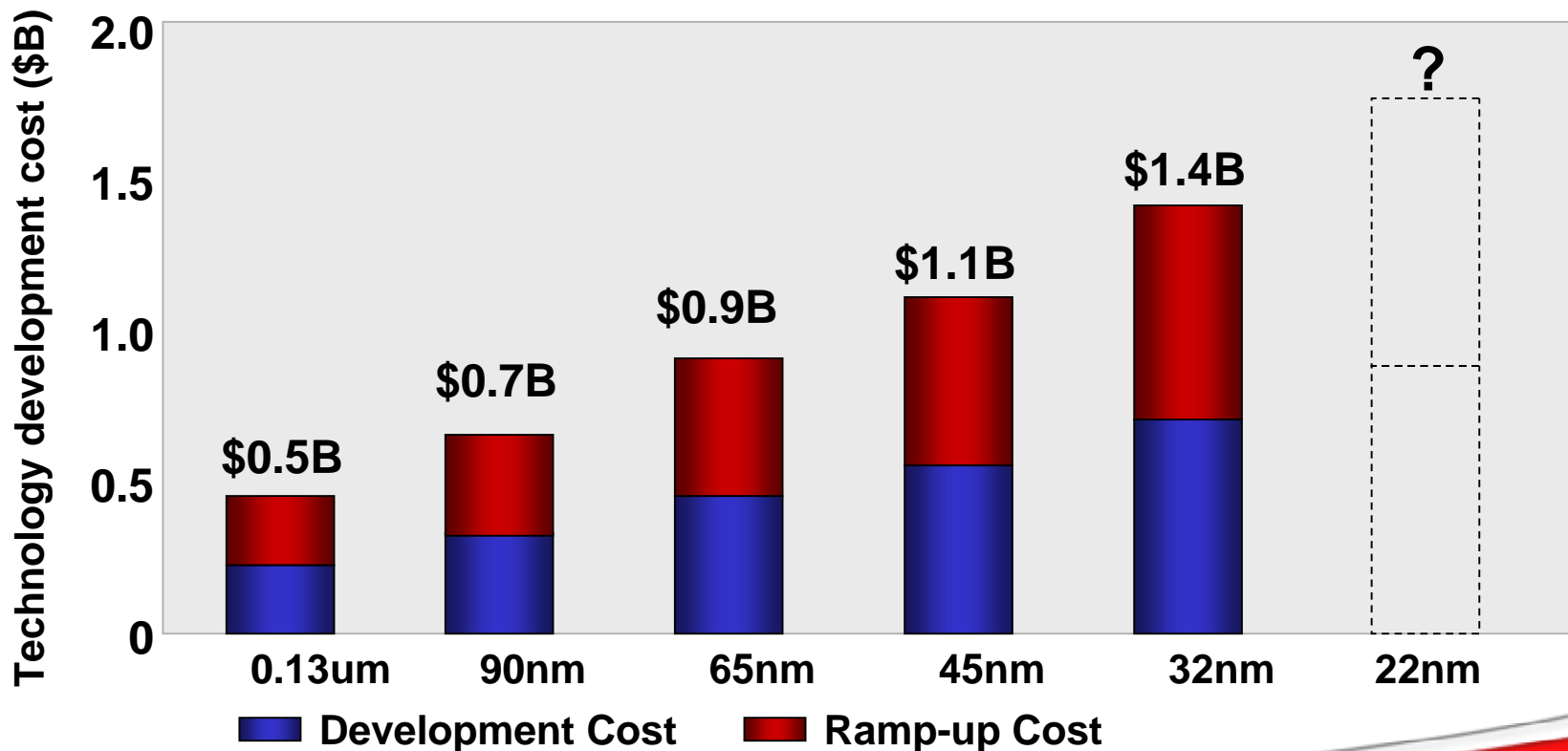
Solution – Foundry Based Business Model

- Many IDMs are changing to either fab-lite or fabless
- A wide variety of consolidation and collaboration are inevitable



2. ROI Risk – Process

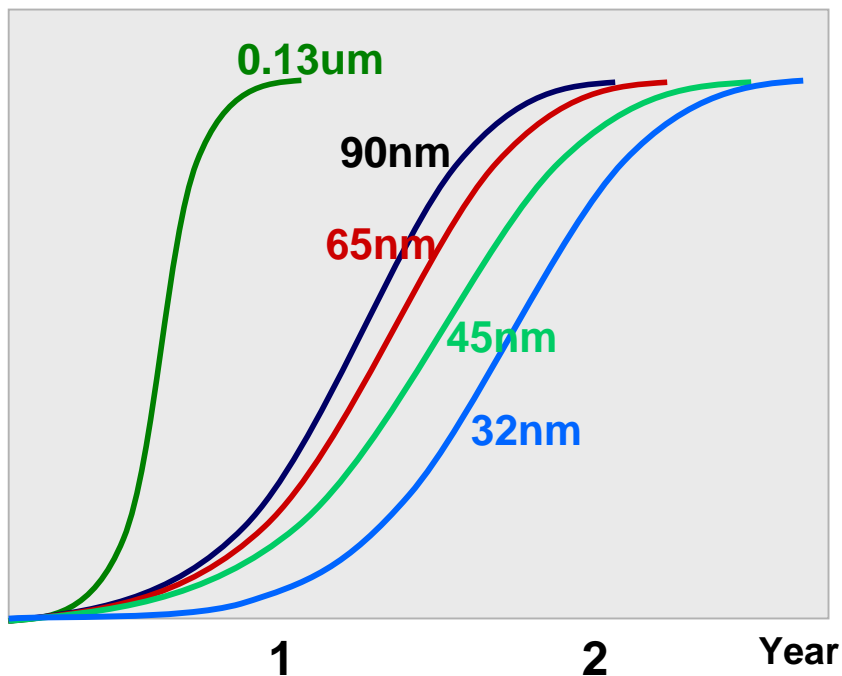
- Incremental challenges in developing next generation processes
- Process technology development costs are continuously increasing



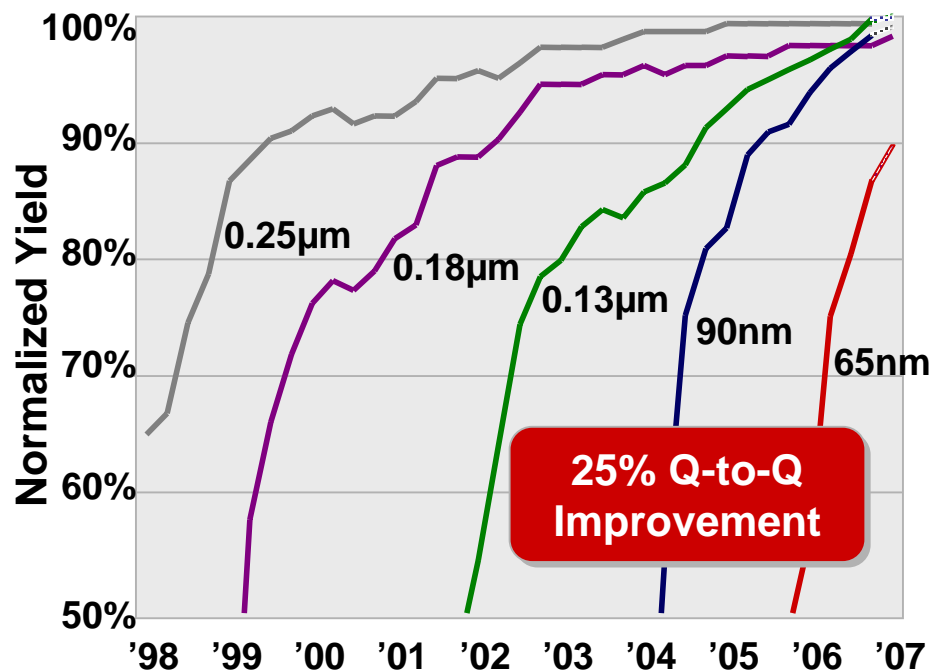
2. ROI Risk – Process (Cont'd)

- Yield ramp-up requires significant time and investment

In-house manufacturing
with limited products



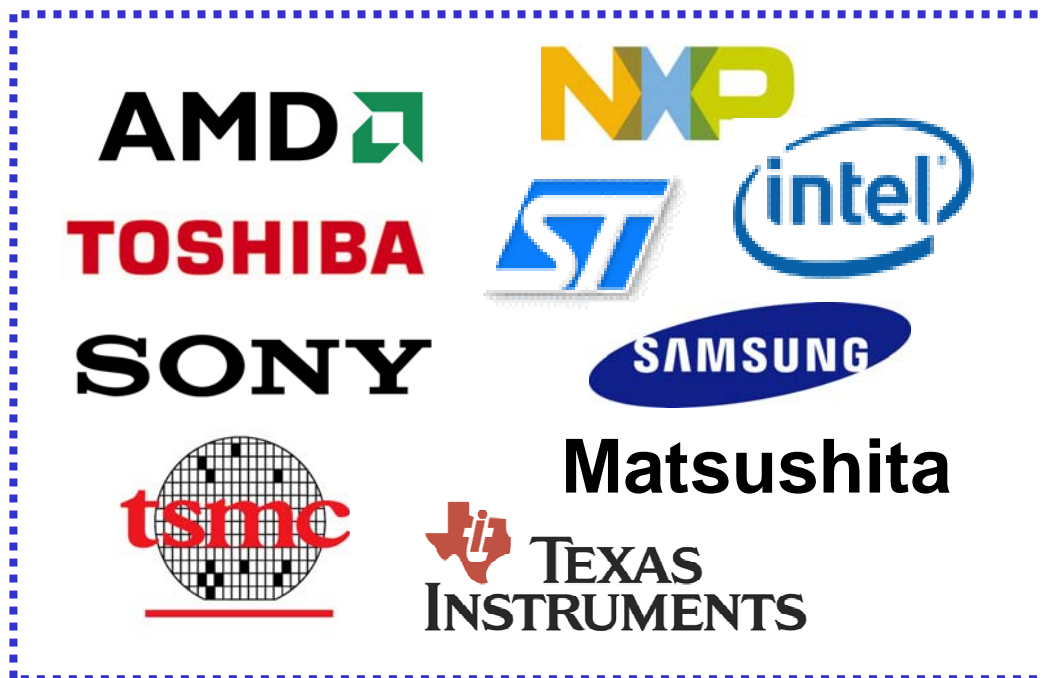
Foundry has the economy of scale



Solution I – Technology Alliance

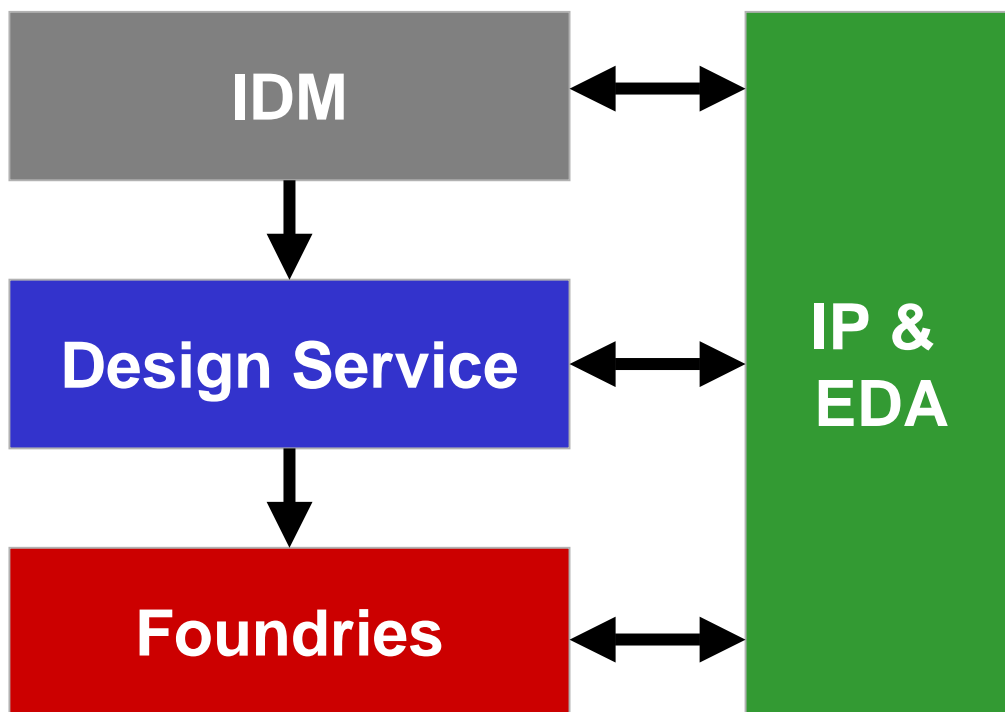
- Collaboration is required to overcome ever – increasing financial as well as technical challenges

IMEC



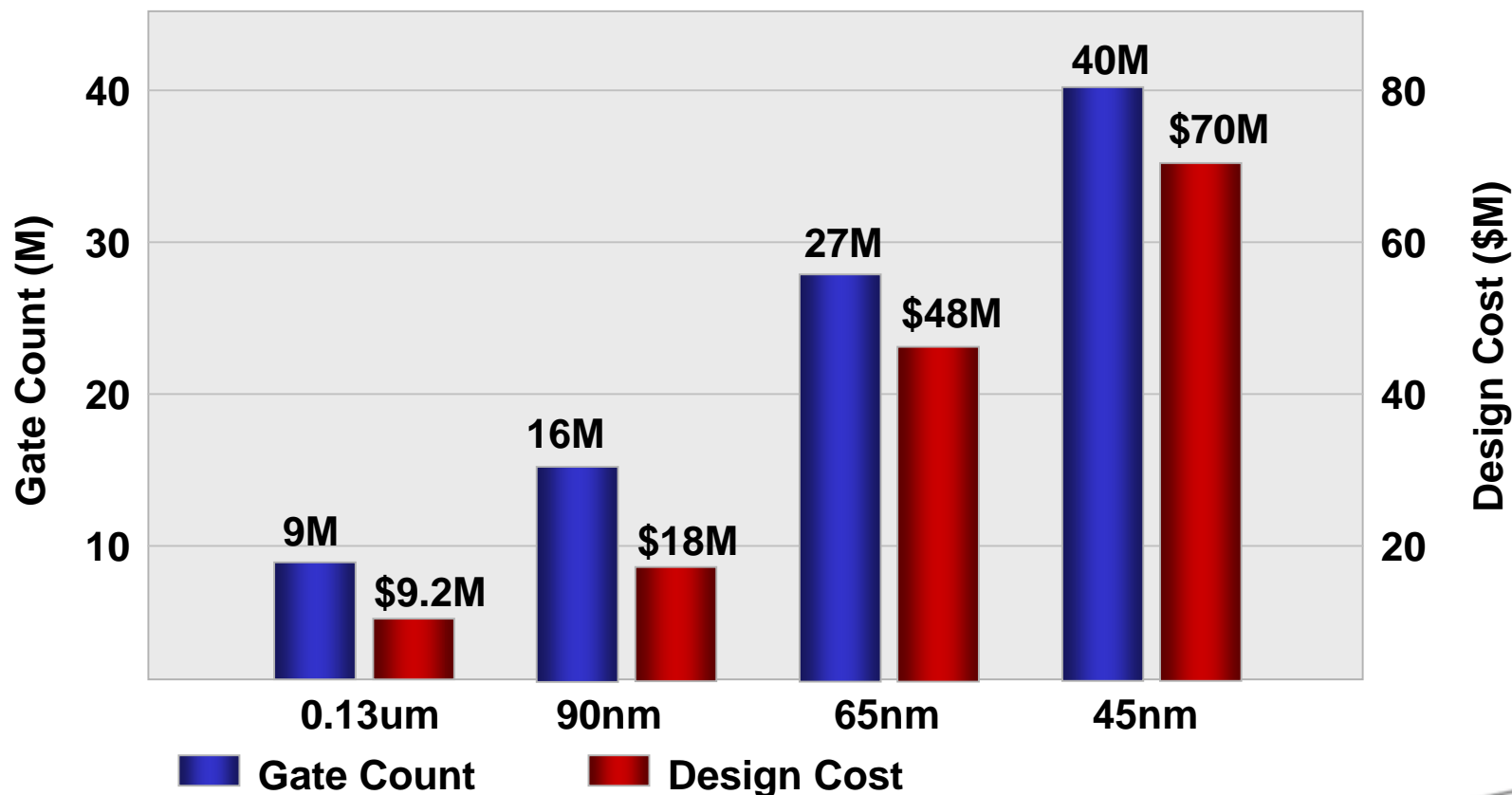
Solution II – Collaboration among Foundry, IP/EDA Vendors, And Design Service Suppliers

- Standardization of IP & EDA tools



3. ROI Risks - Product

- Design complexity and cost increase rapidly
- Short time to market



Solution - Product

- Optimal system partition
- Foundry
 - Design Infrastructure
 - ◆ SPICE
 - ◆ PDK
 - ◆ Foundation IP
 - Prototyping
 - ◆ Cybershuttle
 - ◆ MLM

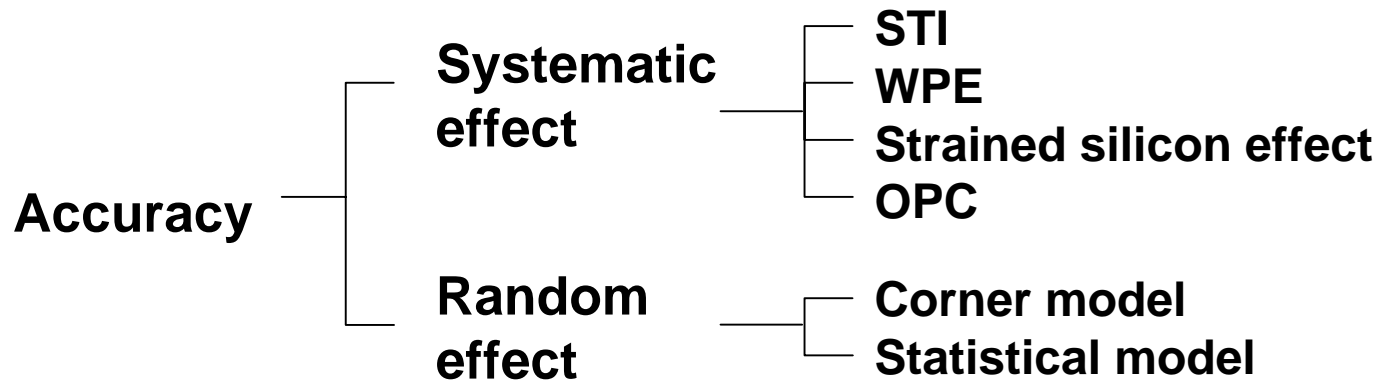
Minimize the product risk and NRE

4. Nanometer Manufacturing

- **New materials and device structure**
 - High-K gate dielectric
 - Metal gate
 - 3D FINFET
 - Low-K Interconnect
- **New EDA solutions for technology modeling and advanced lithography**

Solution – Technology Modeling / Advanced Lithography

- Secure accurate SPICE modeling



- Modeling in new material, 3D device and equipment / topography
- Polarization, OPC, double exposure and mask 3D effects

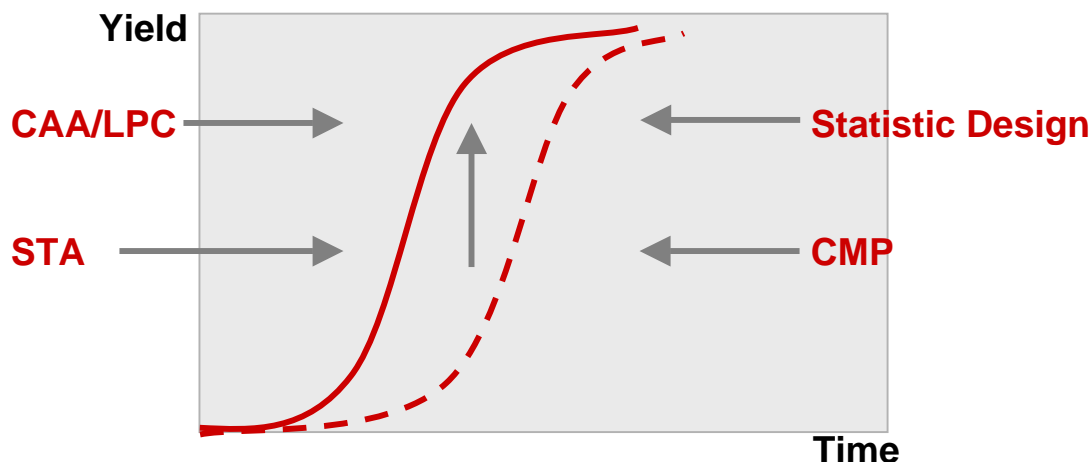
Collaborate with EDA vendors to achieve seamless interfacing hierarchy

5. Design for Nanometer

- **Increasing systematic / parameter / random yield loss due to process variation**
 - Physical patterning effects, open and short, etc.
 - Chemical and mechanical impact, planarity, antenna effect, and via opens, etc.
 - Timing, signal integrity and voltage drop
- **Increasing leakage (quantity, source, variation)**

Solution – Accurate DFM

- Model & simulation-based approach for physical and electrical DFM that represents Manufacturing accurately
 - Physical DFM
 - ◆ Identify hot spot, fix it and improve geometric yield.
 - Electrical DFM
 - ◆ Identify electrical performance deviation, correct it and improve parametric yield



Set-up standard interface between phase and design which is design and layout phase

Solution – DFM Ecosystem

- Foundry to set up DFM ecosystem and open license DUF to reduce cost
- Standard interface between the design infrastructure and manufacturing

Example:



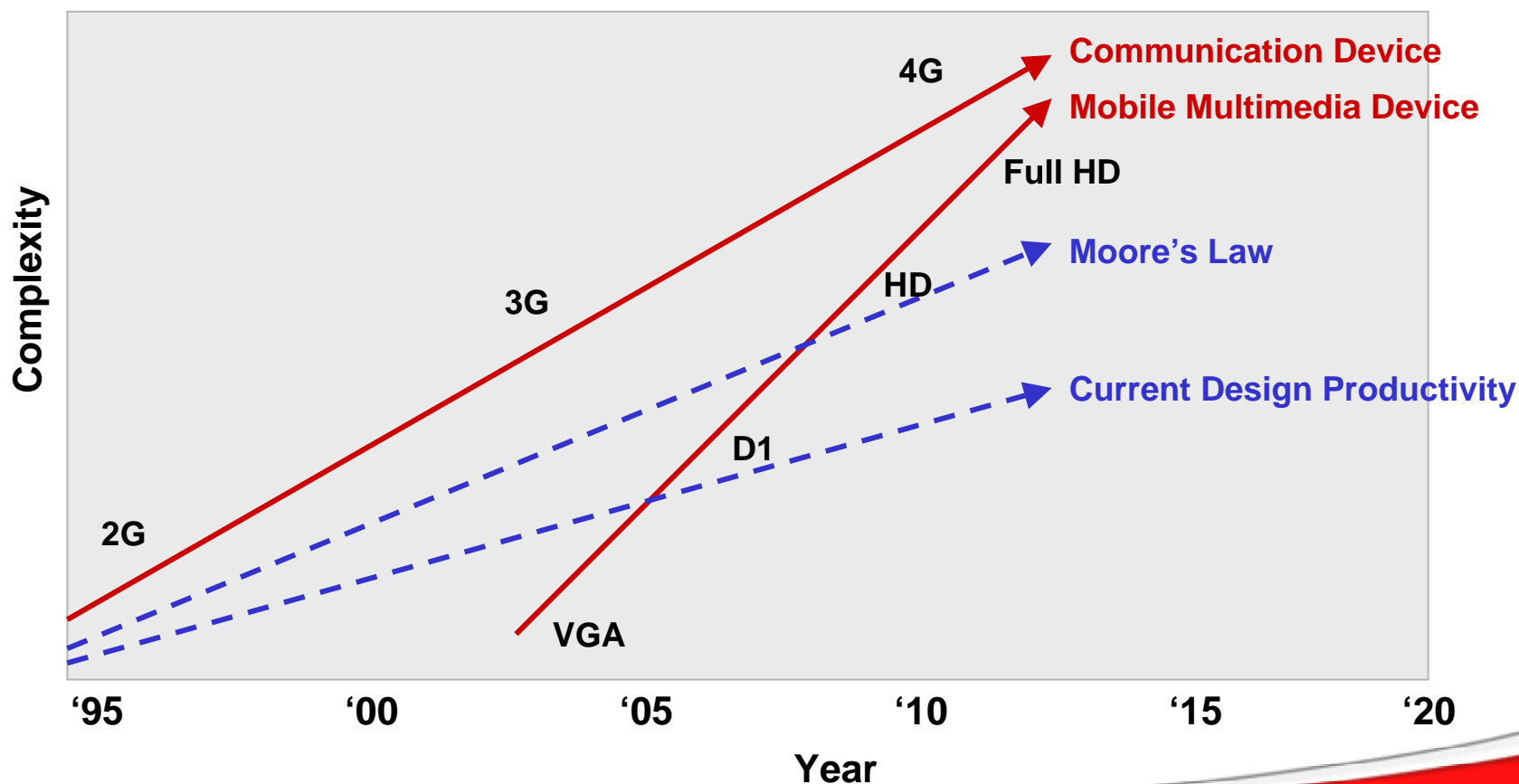
Solution – Low Power

- **Aggressively develop integrated low power solutions for dynamic and leakage power reduction**
 - **Low power process**
 - ◆ Advanced processes with ELK/XLK die-electric: lower voltage, smaller geometry and capacitance for dynamic power reduction
 - ◆ HK/MG and gate CD bias for leakage reduction
 - **Low power IP**
 - ◆ Full set of low power foundation IP, dual power SRAM
 - **Low power design Reference Flow**
 - ◆ Silicon proven design methodologies for TSMC IP and processes
 - ◆ Voltage scaling (DVFS, AVS), power gating with data retention
 - ◆ Low power design automation enabling

Develop vertically integrated solution from system-level to layout and to process

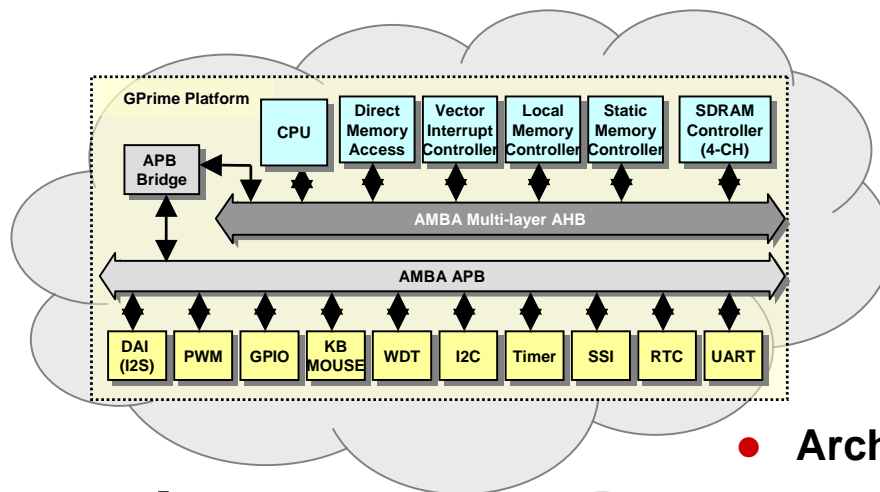
6. Design Complexity

- Increased design complexity causes longer time-to-market and requires significant effort for verification and software design



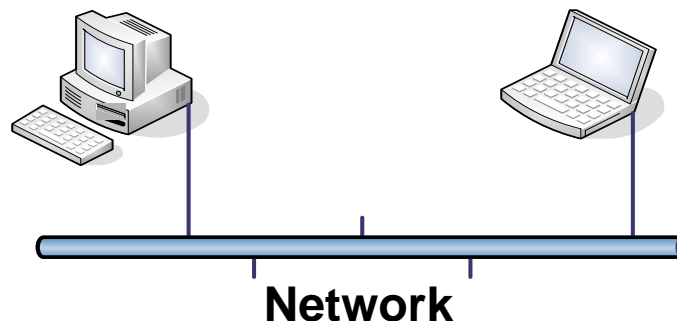
Main Stream vs. ESL Co-development Environment

Main Stream



Electronic
System
Level (ESL)

- Architecture Exploration
- Software Profiling
- Hardware Profiling
- Power Estimation



Solution – ESL

- New ESL design technology to address design complexity, and to provide massively parallel heterogeneous MPSOC design
- SIP and 3D packaging can integrate large capacity memory and analog circuit with short time to market and low cost
- Develop product with chip and PC board at same time to improve success rate

Collaborate with EDA vendors

Summary

- Semiconductor market growth will continue but moderate
- Future growth opportunities will be global but bifurcate
- High ROI risks in design, fab, and technology could be alleviated with the integrated foundry model
- Close collaboration is required between EDA vendors, foundry and IC companies

Thank You

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